Tohoku Univ. Technology

Method of Nitride coating

Nitride can be coated more uniformly

Overview

Conventional nitride coating methods include CVD (chemical vapor deposition) and PVD (physical vapor deposition). However, there is a problem that the manufacturing process is complicated and the work is not efficient because pressure adjustment and atmosphere replacement by vacuum equipment are required.

Therefore, the nitride coating in the atmospheric pressure has been developed, but there is a problem that the surface is uneven.

The present invention shows follow features, and it can solve above problems.

- TiN(Nitride coating) is formed by microwave process.
- Vacuum process is not needed.
- Nitride coating is formed more uniformly.

Product Application

☐ Biomedical and dental implant members

☐ Cutting, Mold instrument, machine tool

IP Data

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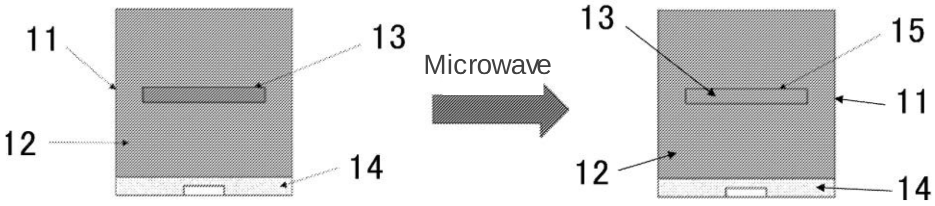
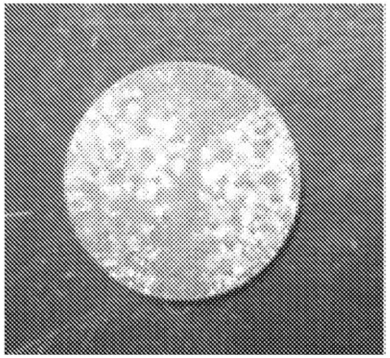
Admin No. : T18-275

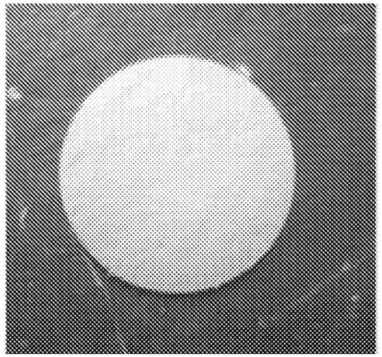
Features･outstandings



11.Container 12. Nitride Powder
13.Substrate 14.Silica wool 15.Nitride coating



Present invention



Nitride coating is formed more uniformly.

See related information ⇒ T05-101 Nitride coating method

Contact

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